L Number	Hits	Search Text	DB	Time stamp
1	2	<pre>(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:22
2	21	430/313.cor. and 430/328.cxr.	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/21 14:25
3	16	<pre>((((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))) and etch\$3</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:33
4	3	<pre>(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:36
6	0	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/21 14:40
7	11	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:46
8	1	((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:49
9	20		USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 14:54
10	0	k .	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:00

11	586	(430/328.ccls. not 430/313.cor.) not	USPAT;	2003/08/21
1.		((((ultraviolet or uv) with (neon)) and	US-PGPUB;	15:15
1		((cross adj link\$3 or cur\$3 or harden\$3)	EPO; JPO;	
		with (polymer\$7 or photopolymer\$7 or	IBM_TDB	
		photoresist or resist))) and ((Ar or		
		argon or inert) with (flow or flowrate or		
		rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)		
		with (flow or flowrate or rate))) not		
		(((430/328.ccls. not 430/313.cor.) and		
		(((Ar or argon) and (Ne or neon)) same		
		(flow or flowrate or rate or sccm or		
		slm))) not ((430/328.ccls. not		
	1	430/313.cor.) and ((Ar or argon or inert)		
		<pre>with (flow or flowrate or rate)))) not (((resist or photoresist or</pre>		
		photopolymer\$7) and (((Ar or argon) and		
		(Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm)) same etch\$3) not		
		((430/328.ccls. not 430/313.cor.) and		
		((Ar or argon or inert) with (flow or		
		<pre>flowrate or rate)))) not ((((resist or photoresist or photopolymer\$7) and (((Ar</pre>		
		or argon) and (Ne or neon)) with (flow or		
		flowrate or rate or sccm or slm))) not		
		((430/328.ccls. not 430/313.cor.) and		
		((Ar or argon or inert) with (flow or		
		flowrate or rate)))) not (((resist or		
		<pre>photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or</pre>		
	ļ	flowrate or rate or sccm or slm)) same		
		etch\$3) not ((430/328.ccls. not		
		430/313.cor.) and ((Ar or argon or inert)		
		with (flow or flowrate or rate)))))		
12	377	430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT;	2003/08/21
		430/313.001.)	US-PGPUB; EPO; JPO;	15:40
]		IBM TDB	
13	1	(((((resist or photoresist or	USPĀT;	2003/08/21
		<pre>photopolymer\$7) near3 (develop\$3)) with</pre>	US-PGPUB;	15:43
	i	(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	IBM_TDB	
14	1 1	(((((resist or photoresist or	USPAT;	2003/08/21
	-	photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	15:44
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or	IBM_TDB	
15	0	<pre>cur\$3 or harden\$3))) and etch\$3) and neon (((ultraviolet or uv) with (Ne)) and</pre>	USPAT;	2003/08/21
1 13	'	(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	15:46
]	with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))) and (neon same	IBM_TDB	
		(flow or flowrate))		
16	102	((ultraviolet or uv) with (Ne)) same	USPAT;	2003/08/21
		(inert or Ar or argon)	US-PGPUB; EPO; JPO;	15:47
			IBM TDB	
17	4	(((ultraviolet or uv) with (Ne)) and	USPAT;	2003/08/21
İ		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	15:56
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))) and ((Ar or	IBM_TDB	
		<pre>argon or inert) with (flow or flowrate or rate))</pre>		
18	71	((ultraviolet or uv) with (Ne)) and	USPAT;	2003/08/21
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	16:00
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
1.0		photoresist or resist))	IBM_TDB	
19	4	430/313.cor. and 430/328.cxr. and (etch\$3	USPAT;	2003/08/21
		with chamber)	US-PGPUB; EPO; JPO;	16:06
			IBM TDB	
L	L		721 100	II

1	/
١,	_

22	1	250/504D 504H sala and /noon on Nol with	TICDATE.	2003/08/21
22	4	250/504R-504H.ccls. and (neon or Ne) with	USPAT;	16:09
		(ultraviolet or uv)	US-PGPUB; EPO; JPO;	16:09
			IBM TDB	
_	2	(("20030003407") or ("20030003683")).PN.	USPAT;	2003/01/25
		((20050003407) OI (20050005005)).FM.	US-PGPUB	17:17
_	25384	(resist or photoresist or photopolymer\$7)	USPAT;	2003/01/31
	23304	near3 (develop\$3)	US-PGPUB;	17:10
		Hears (deveropys)	EPO; JPO;	17.10
			IBM TDB	
_	1494	((resist or photoresist or	USPAT;	2003/01/31
	1474	photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	12:06
		(ultraviolet or uv)	EPO; JPO;	12.00
		(dictaviolet of dv)	IBM TDB	
_	38757	(Si or silicon or silicone) with (cross	USPAT;	2003/01/31
] 30,0,	adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	12:07
		day linkys of carys of narachys,	EPO; JPO;	12.07
			IBM TDB	
_	58	(((resist or photoresist or	USPAT;	2003/01/31
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	12:07
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or	IBM TDB	
		cur\$3 or harden\$3))		
_	391	(ultraviolet or uv) with (neon)	USPAT;	2003/02/15
		, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	10:10
			EPO; JPO;	
			IBM TDB	
-	57	((ultraviolet or uv) with (neon)) and	USPAT;	2003/02/15
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	10:11
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))	IBM TDB	
-	2	(((ultraviolet or uv) with (neon)) and	USPAT;	2003/08/21
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	14:19
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))) and (neon same	IBM TDB	
		(flow or flowrate))	_	
_	203	((ultraviolet or uv) with (neon)) same	USPAT;	2003/02/15
		(inert or Ar or argon)	US-PGPUB;	10:12
			EPO; JPO;	
			IBM_TDB	
-	51		USPAT;	2003/01/31
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	15:49
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or	IBM_TDB	
		cur\$3 or harden\$3))) and etch\$3		
-	1644	(resist or photoresist or photopolymer\$7)	USPAT;	2003/01/31
		and ((develop\$3) adj20 (ultraviolet or	US-PGPUB;	17:12
		uv))	EPO; JPO;	
1	<u> </u>	//04	IBM_TDB	0000/07/07
-	84		USPAT;	2003/01/31
		adj link\$3 or cur\$3 or harden\$3)) and	US-PGPUB;	17:14
		((resist or photoresist or	EPO; JPO;	
		<pre>photopolymer\$7) and ((develop\$3) adj20 (ultraviolet or uv)))</pre>	IBM_TDB	
[_	583	(ultraviolet or uv))) 430/328.ccls.	USPAT;	2003/02/01
	303	130/320.0013.	USPAT; US-PGPUB;	14:11
			EPO; JPO;	14:11
			IBM TDB	
_	16	430/313.cor. and 430/328.cxr.	USPAT;	2003/08/21
		111, 515. 551. 414 150, 525. 581.	US-PGPUB;	14:25
			EPO; JPO;	11.20
			IBM TDB	
-	181	(post adj (expos\$ or develop\$4)) adj20	USPAT;	2003/01/31
1		(ultraviolet or uv)	US-PGPUB;	18:11
			EPO; JPO;	
			IBM TDB	
_	49	((post adj (expos\$ or develop\$4)) adj20	USPAT;	2003/01/31
		(ultraviolet or uv)) and ((Si or silicon	US-PGPUB;	18:14
		or silicone) with (polymer\$7 or	EPO; JPO;	
		<pre>photopolymer\$7 or photoresist or resist))</pre>	IBM TDB	

				,
-	21	(((post adj (expos\$ or develop\$4)) adj20	USPAT;	2003/01/31
		(ultraviolet or uv)) and ((Si or silicon	US-PGPUB;	18:30
		or silicone) with (polymer\$7 or	EPO; JPO;	
		photopolymer\$7 or photoresist or	IBM_TDB	
		resist))) not ((silicon or Si) near3 (wafer or substrate))		
	1 5		USPAT;	2003/08/21
-	15	<pre>(((((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon</pre>	US-PGPUB;	14:31
			EPO; JPO;	14.31
		or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or	IBM TDB	
		resist))) not ((silicon or Si) near3	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	
		(wafer or substrate))) and etch\$3		
	9	("4751170" "4931351" "5407786"	USPAT	2003/02/01
		"5427649" "5486424" "5688723"	002111	10:33
	1	"5707783" "5877075" "6190837").PN.		10.33
_	567	430/328.ccls. not 430/313.cor.	USPAT;	2003/02/01
		150, 520, 5625. 1165 160, 616, 661.	US-PGPUB;	14:36
			EPO; JPO;	
	:		IBM TDB	
-	1	(((ultraviolet or uv) with (neon)) and	USPAT;	2003/08/21
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	14:35
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))) and ((Ar or	IBM TDB	
		argon or inert) with (flow or flowrate or	_	
		rate))		
-	12	(430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2003/08/21
		or argon or inert) with (flow or flowrate	US-PGPUB;	14:39
		or rate))	EPO; JPO;	
			IBM_TDB	
-	11	((430/328.ccls. not 430/313.cor.) and	USPAT;	2003/08/21
	1	((Ar or argon or inert) same (flow or	US-PGPUB;	14:46
		flowrate or rate))) not ((430/328.ccls.	EPO; JPO;	
		not 430/313.cor.) and ((Ar or argon or	IBM_TDB	
	_	<pre>inert) with (flow or flowrate or rate)))</pre>		
-	1	((430/328.ccls. not 430/313.cor.) and	USPAT;	2003/08/21
		(((Ar or argon) and (Ne or neon)) same	US-PGPUB;	14:49
		(flow or flowrate or rate or sccm or	EPO; JPO;	
		slm))) not ((430/328.ccls. not	IBM_TDB	
		430/313.cor.) and ((Ar or argon or inert)		
	329	with (flow or flowrate or rate)))	IICDATE -	2002/02/01
_	329	((resist or photoresist or photopolymer\$7) and (((Ar or argon) and	USPAT;	2003/02/01
		pnotopolymers/) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or	US-PGPUB; EPO; JPO;	12:21
		rate or sccm or slm))) not	IBM_TDB	
		((430/328.ccls. not 430/313.cor.) and	12.1_122	
		((Ar or argon or inert) with (flow or		
		flowrate or rate)))		
_	66	((resist or photoresist or	USPAT;	2003/02/01
		photopolymer\$7) and (((Ar or argon) and	US-PGPUB;	16:50
		(Ne or neon)) with (flow or flowrate or	EPO; JPO;	
		rate or sccm or slm))) not	IBM_TDB	
		((430/328.ccls. not 430/313.cor.) and	_	
		((Ar or argon or inert) with (flow or		
		flowrate or rate)))		
-	15	((resist or photoresist or	USPAT;	2003/08/21
		photopolymer\$7) and (((Ar or argon) and	US-PGPUB;	14:52
		(Ne or neon)) with (flow or flowrate or	EPO; JPO;	
		rate or sccm or slm)) same etch\$3) not	IBM_TDB	
		((430/328.ccls. not 430/313.cor.) and		
		((Ar or argon or inert) with (flow or		
l	<u> </u>	flowrate or rate)))	<u> </u>	

	51	(((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:00
	554	with (flow or flowrate or rate))) (430/328.ccls. not 430/313.cor.) not ((((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist)) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not ((((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:11
_	1984	with (flow or flowrate or rate)))) 430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO;	2003/08/21 15:39
_	1	<pre>((((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)</pre>	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:43
-	1		USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:44
-	304	(ultraviolet or uv) with (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/02/15 10:10
	0	<pre>(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:45

_	83		USPAT;	2003/08/21
		(inert or Ar or argon)	US-PGPUB;	15:46
		-	EPO; JPO;	
			IBM TDB	1
_	3	(((ultraviolet or uv) with (Ne)) and	USPAT;	2003/08/21
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	15:55
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	1 10.00
		photoresist or resist))) and ((Ar or	IBM TDB	1
		argon or inert) with (flow or flowrate or	1011_100	1
	İ			1
		rate))		
-	1	("6054379").PN.	USPAT;	2003/02/21
			US-PGPUB	17:30
-	58		USPAT;	2003/08/21
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	15:58
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))	IBM TDB	
-	3	430/313.cor. and 430/328.cxr. and (etch\$3	USPĀT;	2003/08/21
		with chamber)	US-PGPUB;	16:06
			EPO; JPO;	
			IBM TDB	
_	143	430/313,317.ccls. and (etch\$3 with	USPĀT;	2003/02/22
		chamber) not (430/328.ccls. not	US-PGPUB;	17:13
		430/313.cor.)	EPO; JPO;	1,113
		100,01010011,	IBM TDB	
_	101	430/313,317.ccls. and (etch\$3 near3	USPAT;	2003/02/22
	101	chamber) not (430/328.ccls. not	US-PGPUB;	17:19
		430/313.cor.)	EPO; JPO;	17.15
		130/313:601:/	IBM TDB	
_	2231	(resist or photoresist) same	USPAT;	2003/02/22
	2231	((ultraviolet or uv) with etch\$3)	US-PGPUB;	17:23
		((dreravioree or do) wren eccuso)	EPO; JPO;	17.23
	175	((,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	IBM_TDB	1 2002 (02 (22
-	175	(\ \	USPAT;	2003/02/22
		((ultraviolet or uv) with etch\$3)) and	US-PGPUB;	17:22
		430/313,317,328.ccls.	EPO; JPO;	
			IBM_TDB	
_	17	(resist or photoresist) same	USPAT;	2003/02/22
		((ultraviolet or uv) with etch\$3 near2	US-PGPUB;	17:23
		chamber)	EPO; JPO;	
		<u> </u>	IBM_TDB	
_	4		USPAT;	2003/08/21
		(ultraviolet or uv)	US-PGPUB	16:07